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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No.

10/647,985

Confirmation No. 3087

Applicant:

Patricia Beauregard Smith, et al.

Filed:

August 26, 2003

Art Unit:

1746

Examiner:

Zeinab El-Arini

Docket No.

TI-33260

Customer No.

23494

## **INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97 & 1.98**

Commissioner For Patents P.O. Box 1450 Alexandria, VA 22313-1450 MAILING CERTIFICATE UNDER 37 C.F.R. § 1.8(a)

I hereby certify that the above correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on 1-19-06

Ann Trent

Dear Sir:

Applicants wish to bring to the attention of the Patent and Trademark Office the information noted on the enclosed PTO/SB/08A.

In accordance with 37 CFR 1.97 (d), this Information Disclosure Statement is being submitted before payment of the issue fee and is accompanied by the following certification specified in 37 CFR 1.97 (e).

On information and belief, I hereby certify that each item of information contained in this Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.

Pursuant to 37 CFR 1.97 (d), Applicants respectfully petition that this Information Disclosure Statement be considered by the Examiner.

Please charge any shortage in the fees due in connection with the filing of this paper, including extension of time fees, to the deposit account of Texas Instruments Incorporated, Account No. 20-0668, and please credit any excess fees to such Deposit Account.

Respectfully submitted,

Peter K. McLarty

Attorney for Applicants

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Substitute for Form 1449A/PTO			Complete If Known			
			Application Number	10/647,985		
	N DISCLOSURE		Filing Date	August 26, 2003		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT			First Named Inventor	Patricia Beauregard Smith, et al.		
			Group Art Unit	1746		
(use as many sh	eets as necessary)		Examiner Name	Zeinab El-Arini		
1	of	1	Attorney Docket No.	TI-33260		

				U.S. I	PATENT DOCUME	NTS	
	Cite No.1	U.S. Patent Document		Name of Patentee	Date of Pub. of		
Exam. Initials*		Number	Kind Code <sup>2</sup> (if known)	or Applicant of Cited Doc.	Cited Doc. (mm-dd-yyyy)	Pages, Columns, Lines, Where Relevant Passages or Relevant Figu	
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Exam. Initials*	Cite No.1	Office <sup>3</sup>	Number⁴	Kind Code <sup>2</sup> (if known)	or Applicant of Cited Doc.	of Cited Doc. (mm-dd-yyyy)	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	
	ВА							
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		NON PATENT LITERATURE DOCUMENTS	
Exam. Initials*	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
	CA	OKUDA, Seiichiro, et al., "New Dry Tool after Cleaning of Low-k Dielectrics," Solid State Phenomena, Vol. 92, 2003, pp. 287-291, Proceedings of Ultra Clean Processing of Silicon Surfaces Conference, April 15, 2003, Diffusion and Defect Data, Solid State Data, Part B, Vaduz, LI, September 2003.	
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Examiner	Date	
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<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>&</sup>lt;sup>1</sup>Unique citation designation number. <sup>2</sup>Applicant is to place a check mark here if English Translation is attached.